



Plasma Electrolytic Polishing

for SRF

Eduard Chyhyrynets



11th International Workshop on
Thin Films and New Ideas for Pushing the
Limits of RF Superconductivity



Scaling PEP for 1.3 GHz cavities



PEP Validation

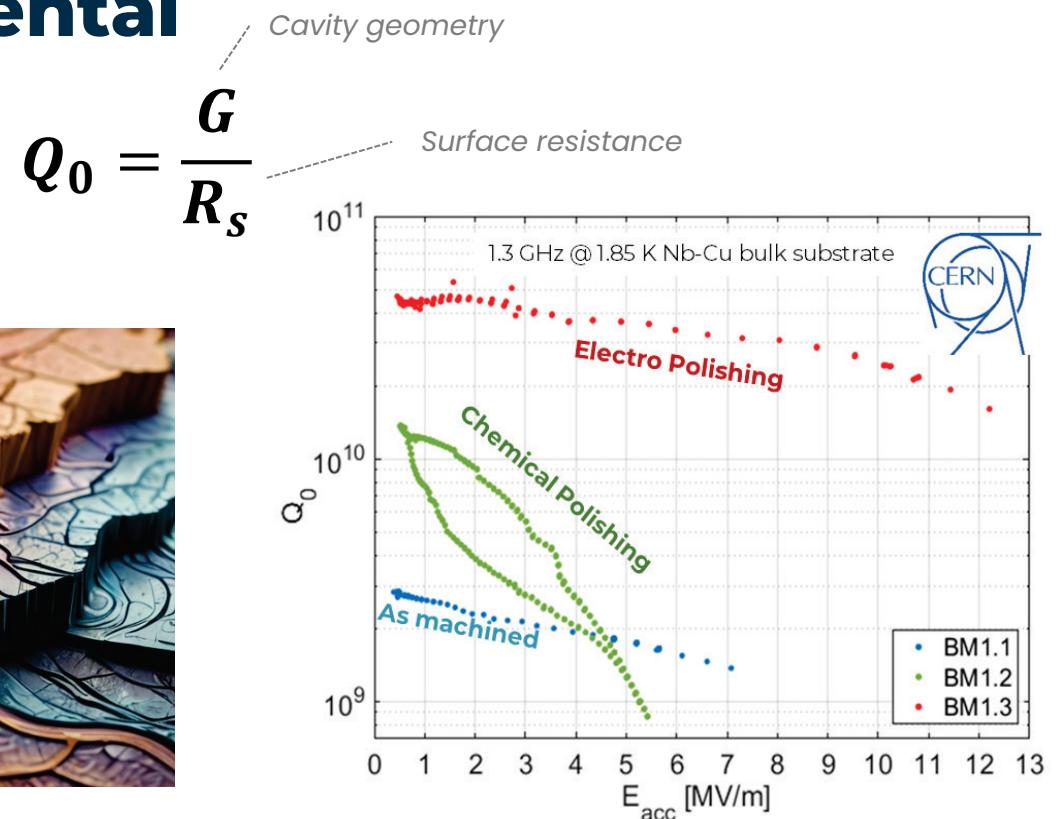
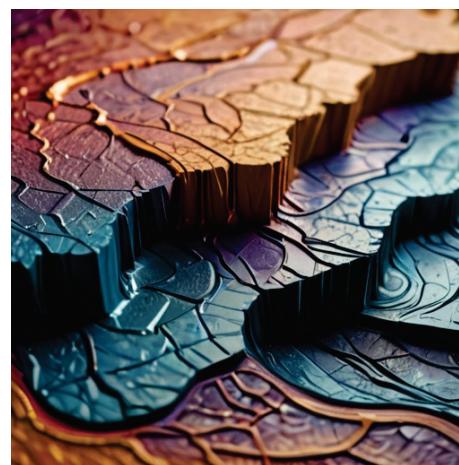
QWR Legnaro Plant



Motivation

➤ **Cu substrate plays a fundamental role in SRF performances**

1. High SRF performance **requires roughness and defects reduction**
2. Thin Film deposits **replicate the substrate**



L.Vega Cid, TTC meeting (elaborated)



Limitations of EP

- ▶ **Concentrated acids** -> Risks
In case of Nb -> use of HF.
- ▶ **Slow polishing rates** -> tens of hours or days
- ▶ **Requires prepolishing** (CBP, tumbling, ecc)

HF



Nb SRF cavity polishing requires hydrofluoric acid (HF)

- ➔ HF is an extremely dangerous and poisoning acid
- ➔ Serious workers hazard risks
- ➔ Expensive procurement and disposal
- ➔ Expensive infrastructure for safe handling



Basics of PEP

- **No Acids** in the chemical bath!
- **No HF** for Nb!
- Easier storage
- Easier and cheaper wastes proceeding

Both micro and macro
roughness is improved significantly

Ra ~ 8 nm!!!

Green

Diluted water solutions,
environmentally friendly

Efficiency

Equal thickness removal
yield lowest roughness
among competitors



PEP > BCP > EP
PEP > SUBU > EP

Fast

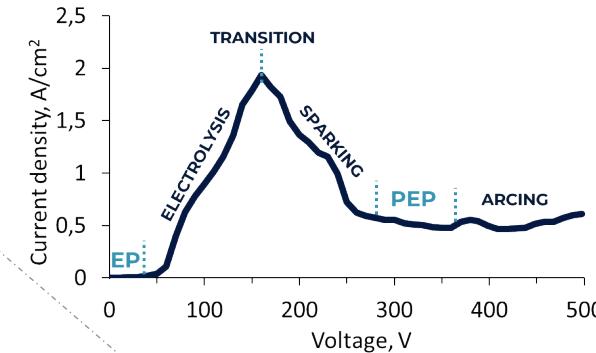
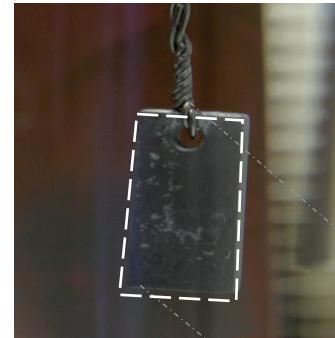
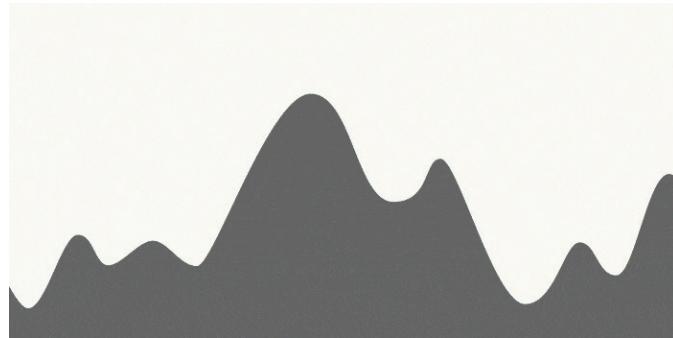
The fastest non-destructive polishing

Versatility

Less sensitive to the cathode shape!
Additive manufacturing compatible



Plasma Electrolytic Polishing

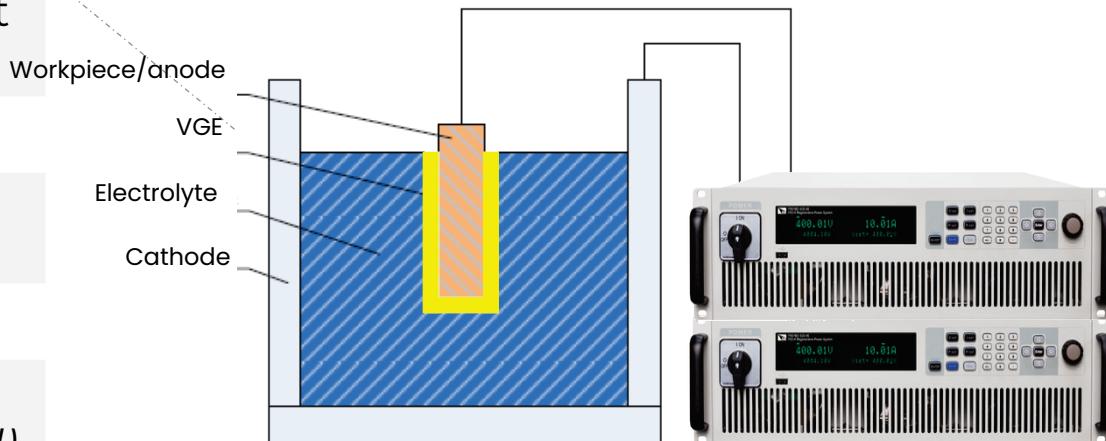


Vapor Gas Layer

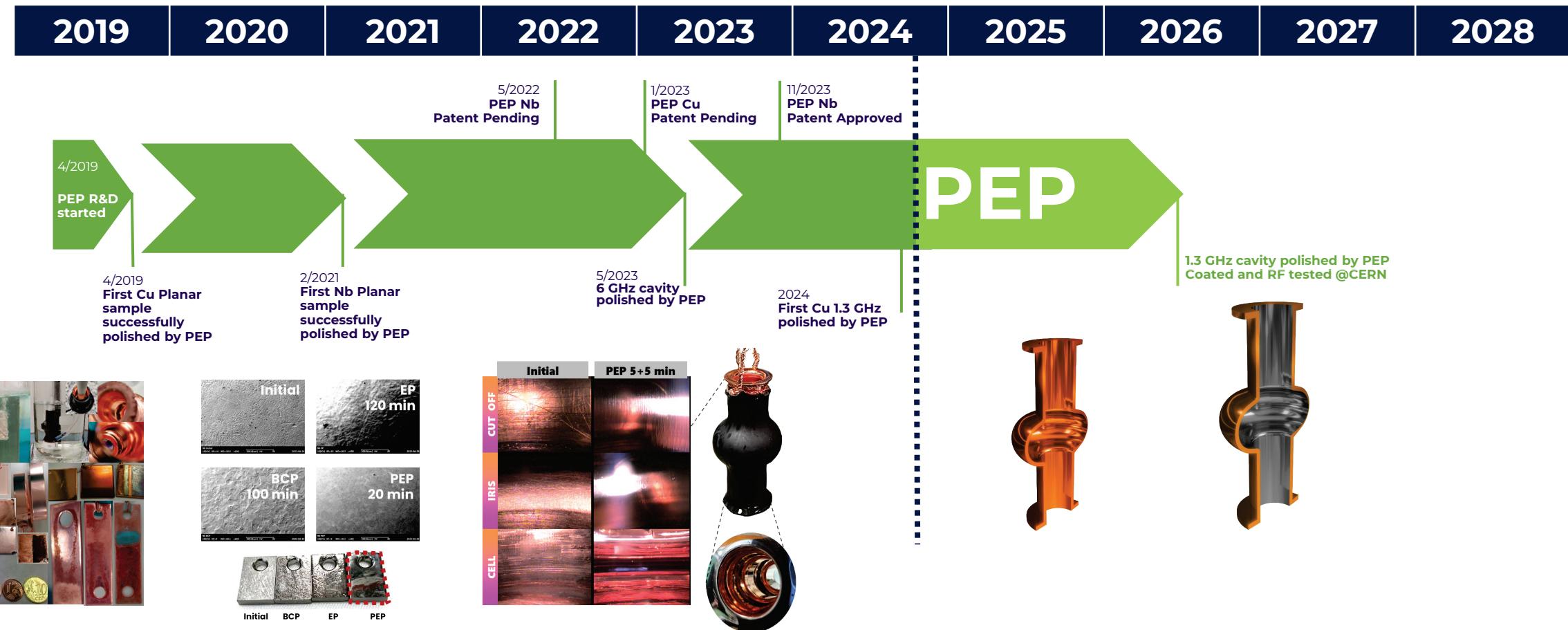
	EP	PEP
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Bath	Concentrated acid solutions	Diluted water-salt solutions
Area cathode: anode	1:1	10:1
Working voltage	2-25 V	260 – 340 V
Current density	0,03 A/cm^2	0,1-0,8 A/cm^2
Temperature	4-60 C° (lower is better)	70-90 C° (high T is required)

Electrochemical method of polishing
A special case of anodic dissolution

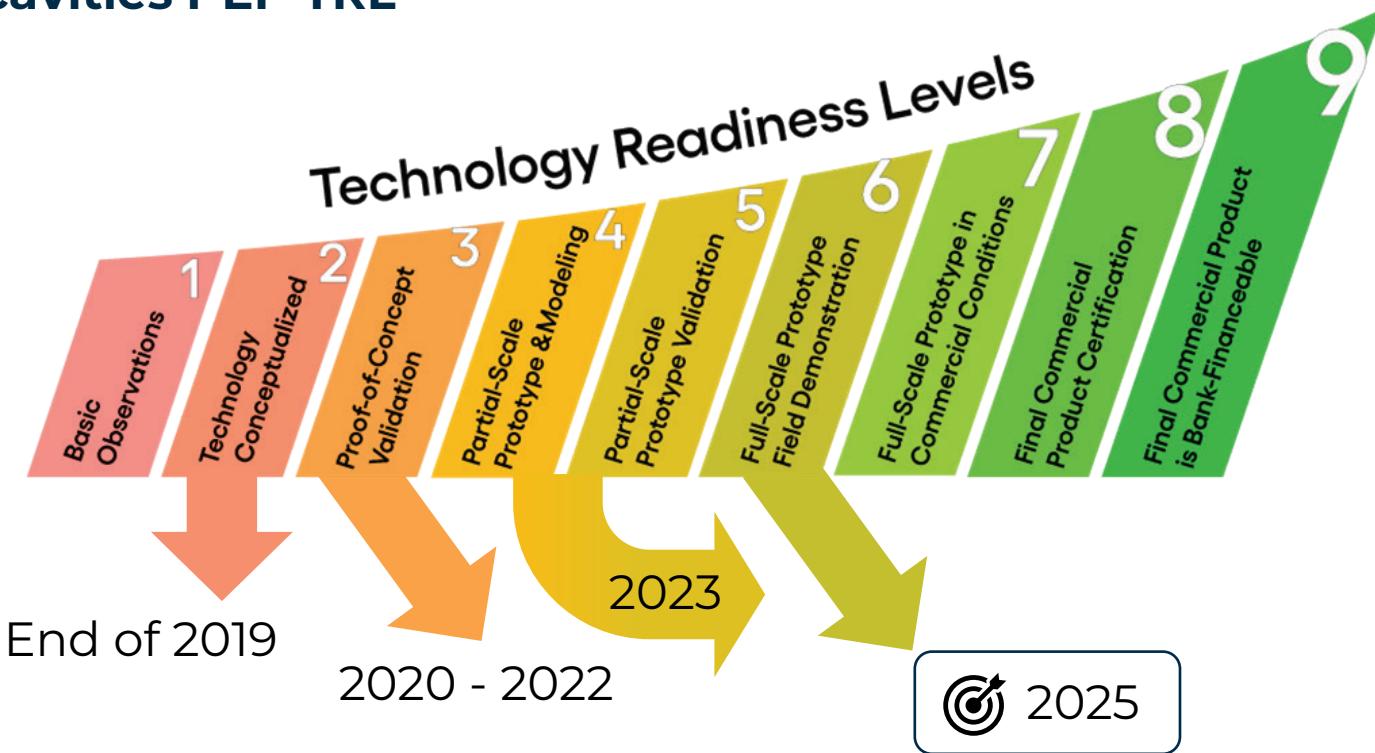


LNL Timeline



TRL Evolution

Cu Elliptical cavities PEP TRL



- Main goal to PEP a 1.3 GHz Cu cavity
- Remove 150 – 200 µm



Scaling challenges



High current densities (Power modes)



Technological scale (volume + surface area)



Process substrate orientation

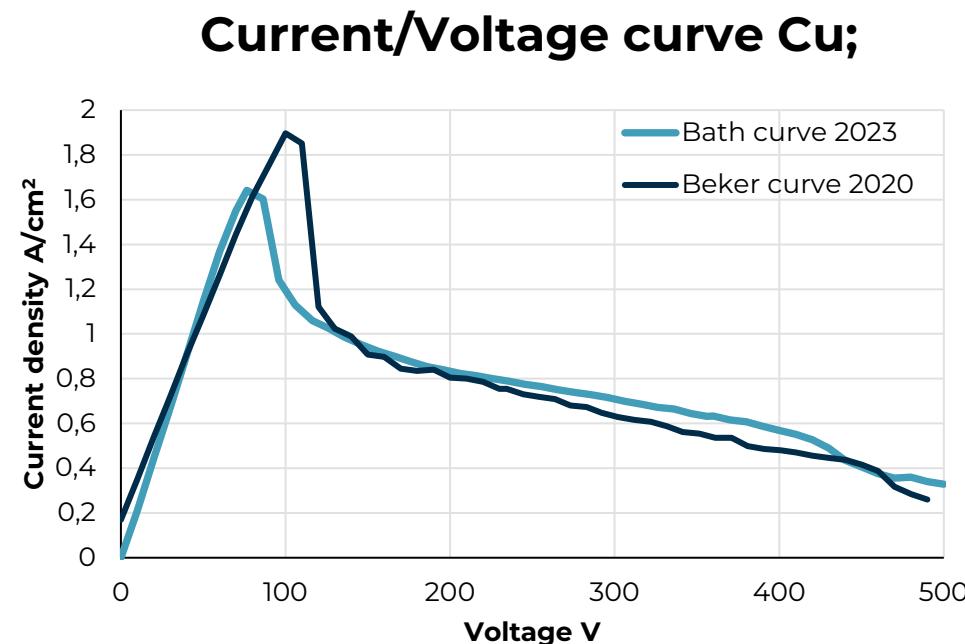


Current density

0,1 – 0,6 A/cm²

40 cm²
in **30 L** bath

12 cm²
in **5 L** bath

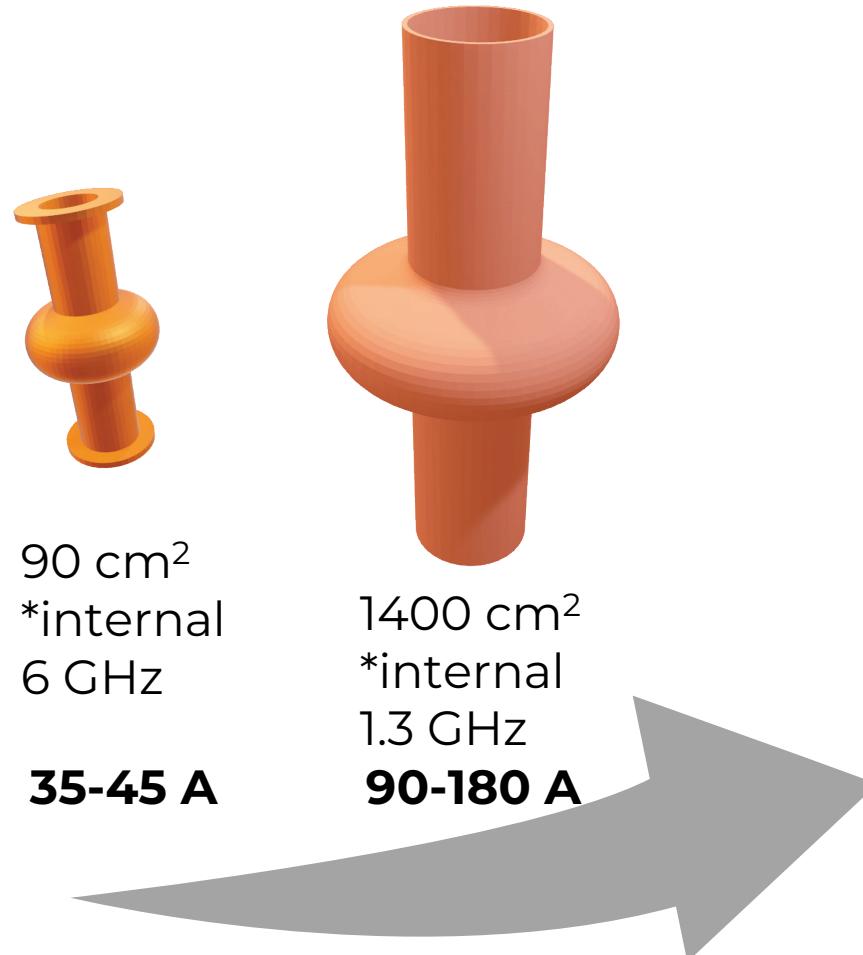
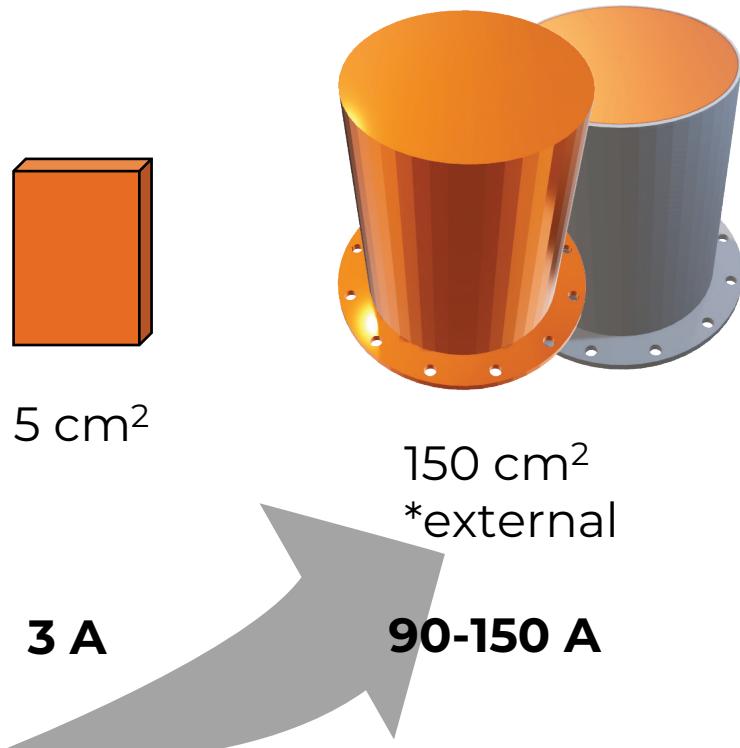


Similiar / Same behaviour after scaling



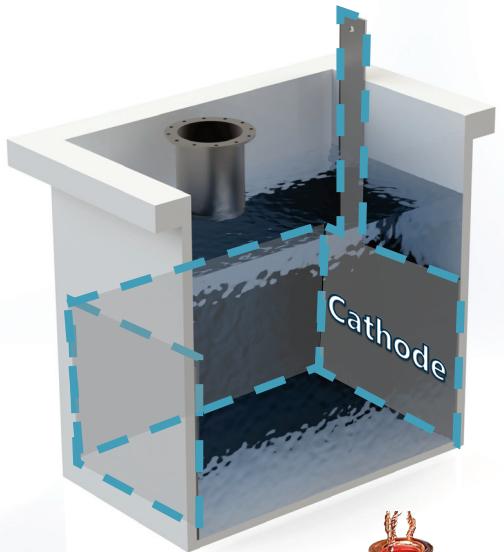


Current density





1.3 GHz Adoption



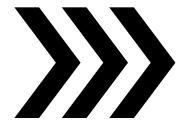
30 L



6 GHz Cu validation



E. Chyhyrynets et. al @ SRF'23



No internal cathode!



300 L

QWR plant @ LNL

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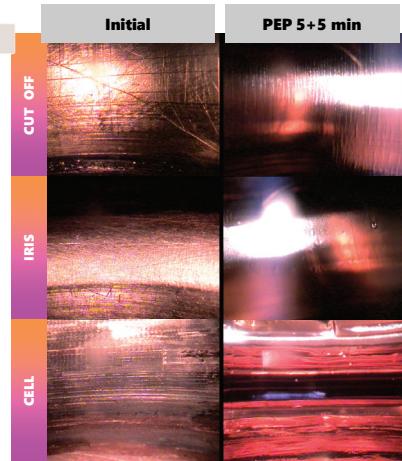
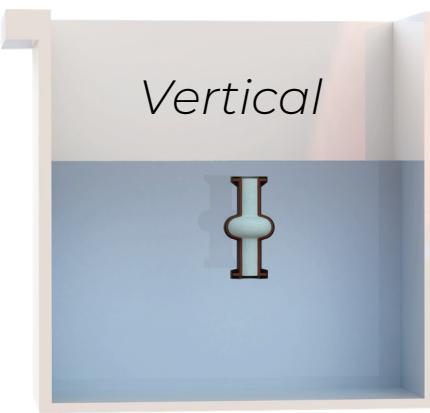
INFN



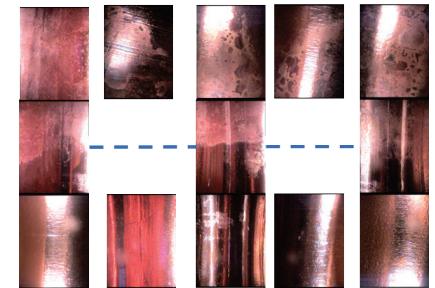
Orientation

From 6 GHz Cu experience

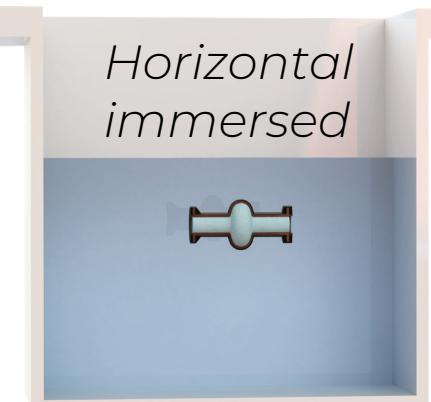
1



2



3





Orientation

1



👍 **Simpler** setup

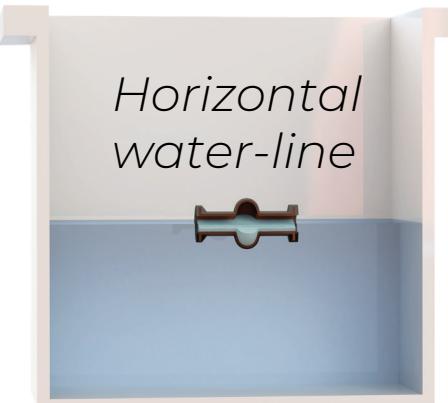
👍 All surface polishing

👎 Possible non-uniformity

👎 Higher current regimes

👎 Needs rotation

2



- 👍 **Uniform** polishing
- 👍 **Half currents** regime

👎 Water line control during process

👎 Rotation mechanism

👎 Lower speeds

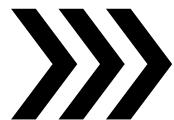
👎 Stains of oxidation

👎 Longer process



Validation

1.3 GHz cavity sample

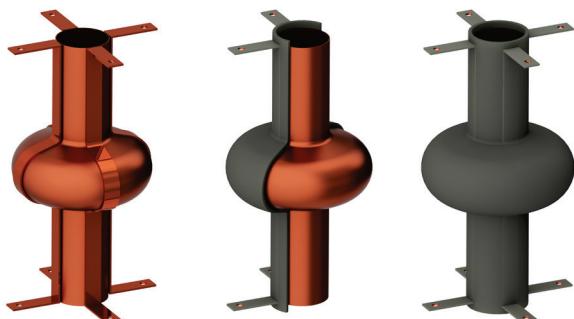


Process parameters

Voltage 300 V

Surface area 1400 cm²

Currents 90-190 A (0,06 – 0,13 A/cm²)



External isolation



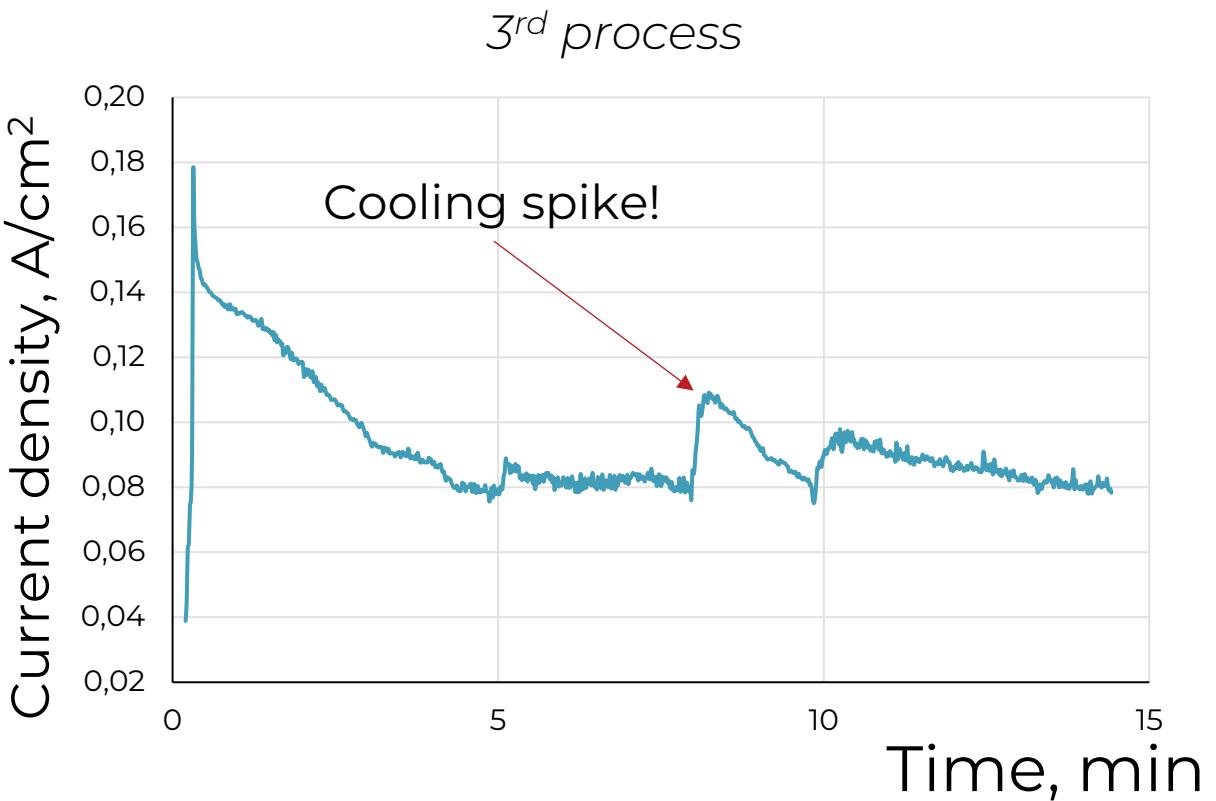
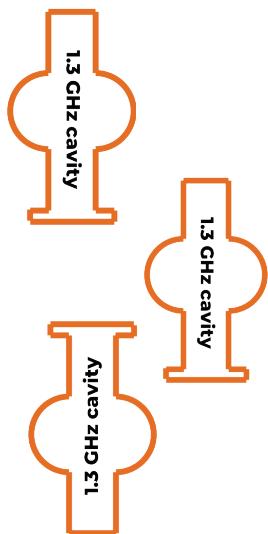


Validation

1.3 GHz cavity sample

3 process

#	Time	RR	Thickness
1	15 min	5,1 µm/min	79 µm
2	6 min	5,4 µm/min	35 µm
3	14,5 min	5,2 µm/min	75 µm
TOT	35,5 min	5,4 µm/min	190 µm





Resulting surface

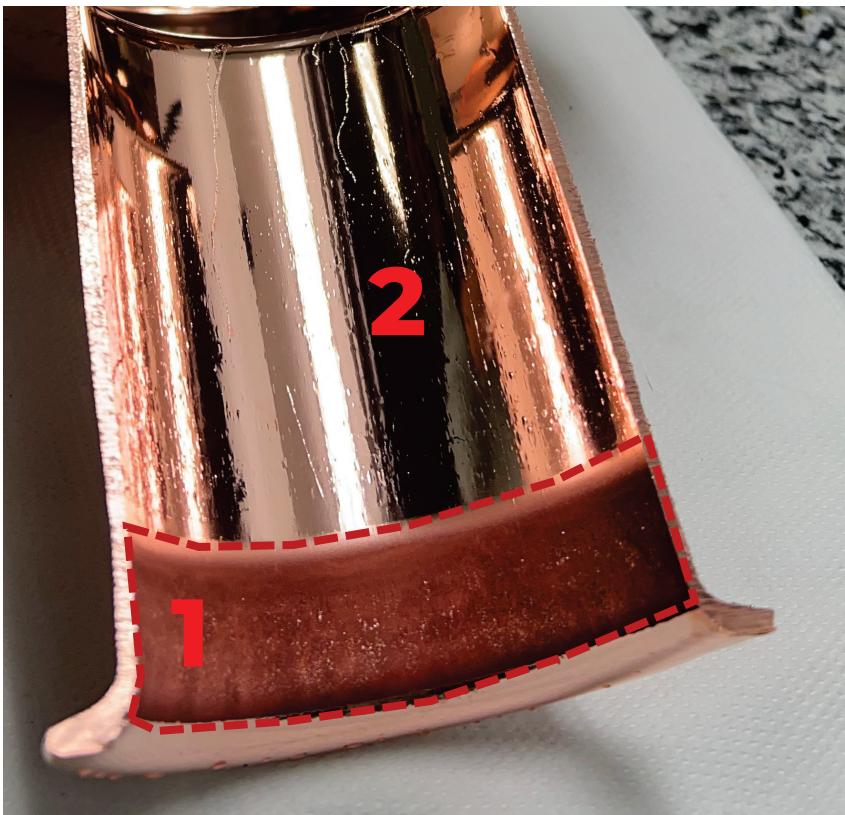
After 3° process





Photo + Issues

1.3 GHz cavity sample



1. Etched zone



2. Glue Residue Marks



Heat-shrink tubing use



1. Unclear nature
2. Sometimes appear
3. To be studied more



Plastic (PVDF, ecc) isolation alternative

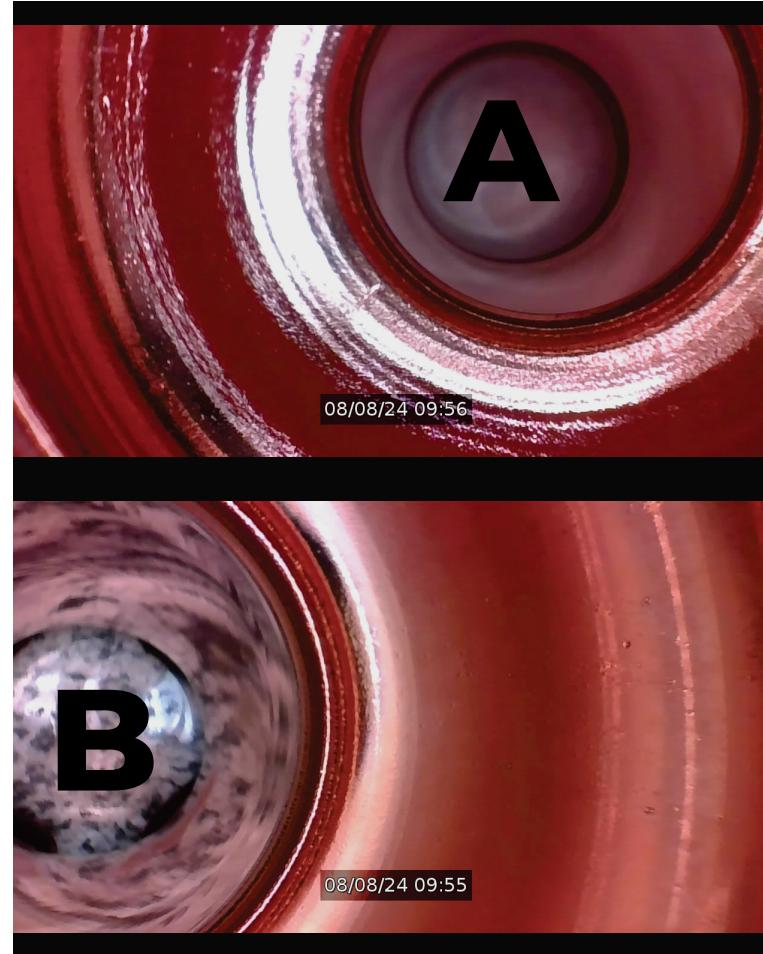
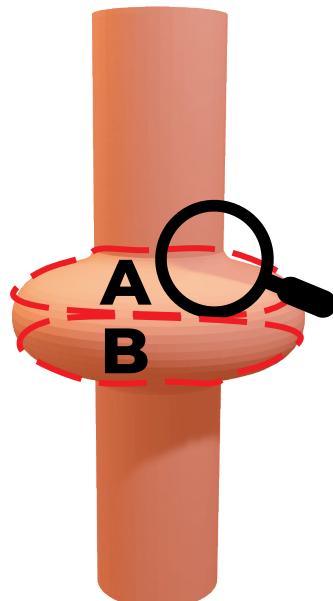
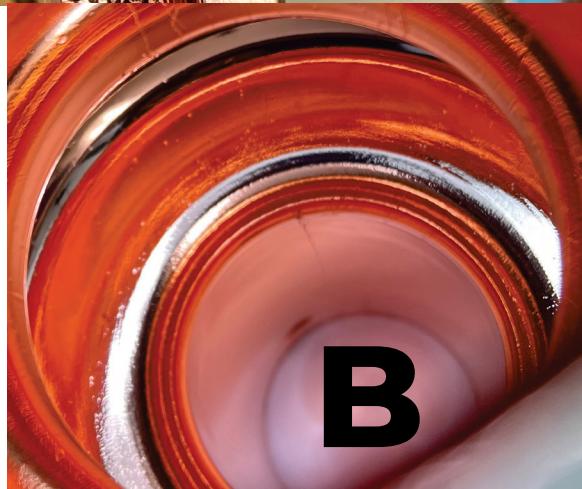


Thermoshrinking isolation without glue



Photo + Issues

1.3 GHz cavity sample





Energy consumption

1.3 GHz cavity sample

	EP	PEP
A, Area	500 cm ²	1400 cm ²
V, Voltage	4 V	18 V
i, Current density	0,02 A/cm ²	0,02 A/cm ²
PR, Polishing rate	0,16 µm/min	0,25 µm/min
Time, τ to remove 200 µm	20h:50min	13h:18min
P, Total Energy	$P' = V \cdot i \cdot A \cdot \tau$	
	0,67 kwh (1,87 kwh')	2 kwh
Ratio	0,9 x	1 x
	QWR @LNL	1.3 GHz @CERN
		1.3 GHz @LNL

Not included:



Cooling for EP



Pre-heating water PEP



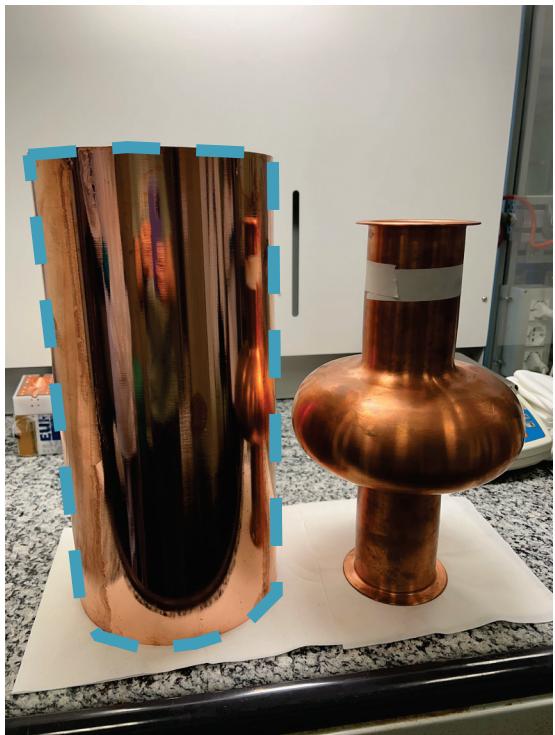
Heat loss

Ferreira et. al
<https://dx.doi.org/10.2139/ssrn.4682212>



Proof of concept

Pushing the limits



Surface area >> 1.3 GHz



Process parameters

Voltage 300 V

Surface area 2350 cm²

Time 7 min

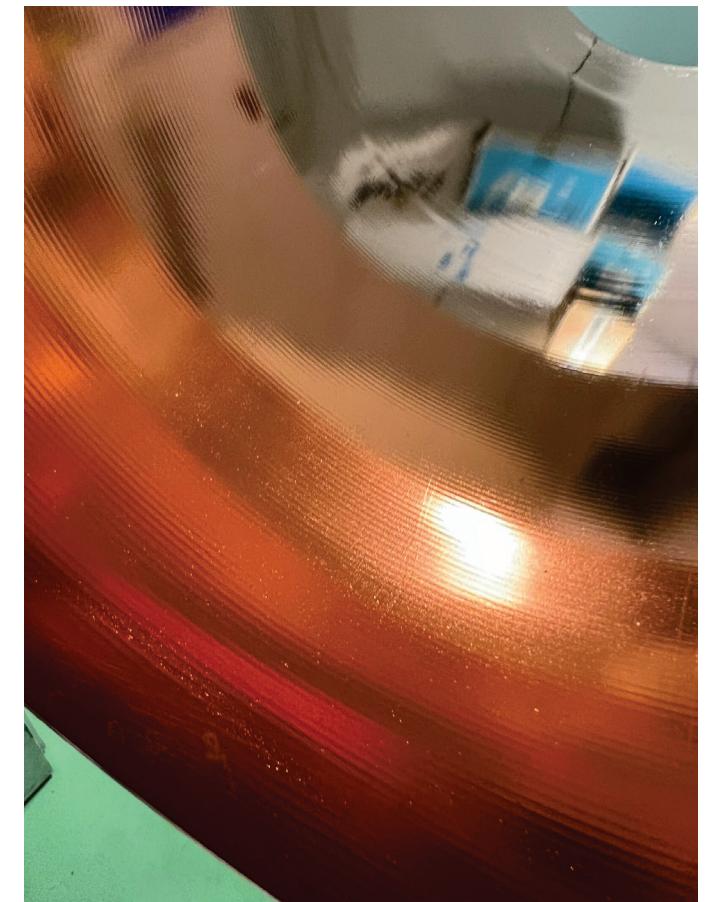
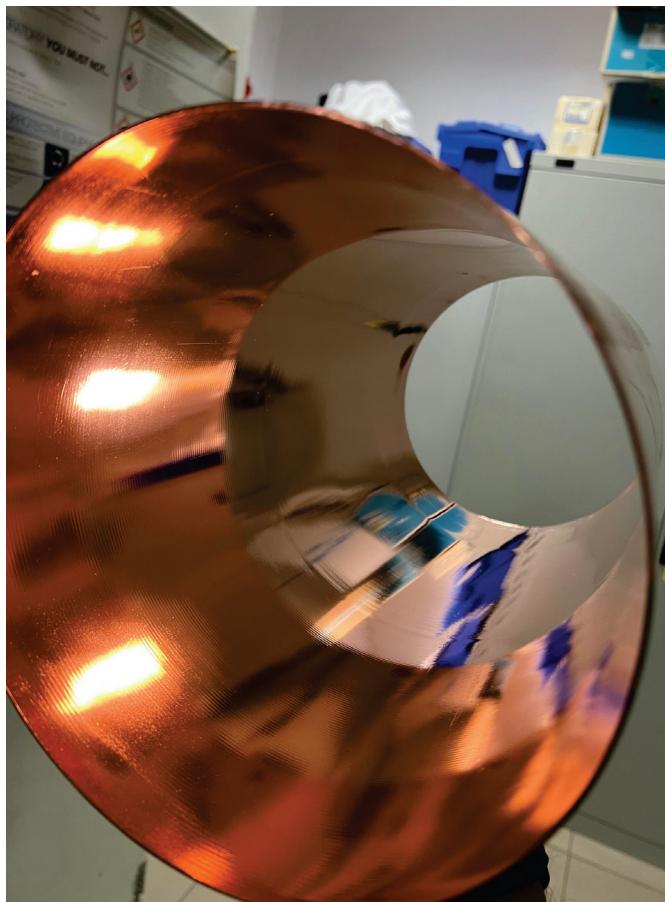
Current 150-160 A (0,06 – 0,07 A/cm²)

	Expected	Measured
Δm , g	80	69
δ , μm	40	32
PR, $\mu\text{m}/\text{min}$	5	4,6
I, A	220	150-160
i, A/cm ²	0,08	0,06 – 0,07



Proof of concept

Pushing the limits





Proof of concept

Can we push more? 400 MHz ?



400 MHz ?

expected

Cylinder	400 MHz
Area, cm ²	12 000
PR, µm/min	4
I, A	600 A
i, A/cm ²	0,055

Conclusions



First **successfull demonstration** of 1.3 GHz Cu **PEP**



Polishing rate **5 µm/min**



11x higher total **energy** consumtion



PEP can be scaled even further.

**Thank you for
your attention!**